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(54) Title: SELECTIVE ETCHING OF A MATRIX COMPRISING SILVER NANO WIRES

(57) Abstract: The present invention refers to a method for selectively structuring of a polymer matrix comprising AgNW (silver nano wires) or CNTs (carbon nanotubes) or comprising mixtures of AgNW and CNTs on a flexible plastic substructure or solid glass sheet. The method also includes a suitable etching composition, which allows to proceed the method in a mass production.



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